

Special Issue

Pattern Recognition Based on Machine Learning and Deep Learning

Message from the Guest Editors

This Special Issue aims to collect high-quality review papers from the fields of pattern recognition research. We encourage researchers from various fields within the journal's scope to contribute review papers highlighting the latest developments in their research field, or to invite relevant experts and colleagues to do so. Topics of interest for this Special Issue include, but are not limited to:

- Signal processing and control;
- Brain-computer interface;
- Image processing;
- DL-based theories, scenarios, and architectures of application placement;
- Artificial intelligence;
- ML-assisted intelligent detection;
- ML algorithm improvement and application.

Guest Editors

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About the Journal

Message from the Editor-in-Chief

As the world of science becomes ever more specialized, researchers may lose themselves in the deep forest of the ever increasing number of subfields being created. This open access journal Applied Sciences has been started to link these subfields, so researchers can cut through the forest and see the surrounding, or quite distant fields and subfields to help develop his/her own research even further with the aid of this multi-dimensional network.

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